



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Smith, et al.

Docket No: TI-25250

Serial No: 09/199,829 ✓

Examiner: K. Eaton

Conf. No: 4119

Art Unit: 2823

Filed: 11/25/98

For: HYDROGEN PLASMA PHOTORESIST STRIP AND POLYMERIC RESIDUE  
CLEANUP PROCESS FOR OXYGEN-SENSITIVE MATERIALS

2823  
12/18/01  
Ett. ①  
chusa  
7-23-01

EXTENSION OF TIME

Assistant Commissioner For Patents  
Washington, DC 20231

**MAILING CERTIFICATE UNDER 37 C.F.R. §1.8(a)**

I hereby certify that the above correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, DC 20231 on 7-13-01.

*Ann Trent*  
Ann Trent

Dear Sir:

Pursuant to 37 CFR 1.136(a), Applicants respectfully petition the Commissioner for an extension of the shortened statutory period for response in the above identified Application.

The fee for this extension is indicated below:

X One Month (\$110)

\_\_\_ Three Months (\$890)

\_\_\_ Two Months (\$390)

\_\_\_ Four Months (\$1,390)

Any further necessary extension of time is hereby requested. Charge any and all fees, or credit any overpayment, to the deposit account of Texas Instruments Incorporated, Account No. 20-0668. **This form is submitted in duplicate.**

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01 FC:115 110.00 CH

Texas Instruments Incorporated  
P.O. Box 655474, MS 3999  
Dallas, TX 75265  
(972) 917-4258

Respectfully submitted,

✓ *Peter K. McLarty*  
Peter K. McLarty  
Agent for Applicants  
Reg. No. 44,923

TECHNOLOGY CENTER 2800

JUL 19 2001

RECEIVED